



Docket No.: A-71730/MSS (463035-878)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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|-----------------------|---|----------------------|
| First Named Inventor: | Yoshihide Senzaki | |
| Appln. No.: | 10/656,628 | |
| Filing Date: | September 5, 2003 | Examiner: n/a |
| | Low Temperature Deposition of Silicon Based Thin Films by Single-Wafer Hot-Wall Rapid Thermal | |
| Title: | Chemical Vapor Deposition (RTCVD) | Group Art Unit: 2812 |

PETITION FOR EXTENSION OF PERIOD FOR RESPONSE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Pursuant to 37 C.F.R. § 1.136(a), Applicant hereby petitions for an extension of 3-month(s) (from February 23, 2004 to May 24, 2004 (since May 23, 2004 was a Sunday)) within which to respond to the Notice to File Missing Parts dated December 23, 2003. A check in the amount of \$580.00 (\$475 for 3 month extension fee for small entity; \$65 for Missing Parts; \$40 for Assignment recordation;) is enclosed herewith to cover the extension fee. Please charge any additional fees or credit any overpayment to our Deposit Account No. 50-2319 (Order No. A-71730/MSS (463035-878)).

Respectfully submitted,
DORSEY & WHITNEY LLP

Date: May 24, 2004

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